

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
1	BRS	L1	567	gate same source same drain same (sidewall or spacer) same ((stress or buffer) adj3 layer) same (semiconductor or substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/04/25 19:07			
2	BRS	L2	233	1 same etch\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/04/25 19:08			
3	BRS	L3	131	2 and @pd<="20031114"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/04/25 19:32			
4	BRS	L4	7	CHO-YONG-JOON.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/04/25 19:33			
5	BRS	L5	44	KIM-YOUNG-HEE.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/04/25 19:35			
6	BRS	L6	21	YUN-YOUNG-HWAN.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/04/25 19:36			
7	BRS	L7	4	BAEK-DOO-HEUN.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/04/25 19:37			